MACROMOLECULAR MATERIAL ABSORBING SHORT-WAVE LIGHT

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Inventor: SHIMOMURA TAKESHI; others: 02

Applicant: TERUMO CORP

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- european:

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Abstract of **JP1207310**

PURPOSE:To obtain the title material absorbing excimer laser beam capable of etching with a short time exposure and having resistances to etching, consisting of methacrylate, fluoromonomer and a specific aromatic monomer.

CONSTITUTION:The aimed material expressed by the formula (R1, R3 and R5 are H, methyl and ethyl, respectively; R2 is 1-5C alkyl; R4 is fluoroalkyl at least one H is substituted with F within 1-8C alkyl) R6 is a group containing aromatic chain such as naphthalene ring, anthracene ring; l, m and n >=1, respectively and 30<=(l+m)/n<=200). The material is preferably obtained by copolymerization with plasma polymerization method of the three; methacrylate such as methyl methacrylate, fluoro-monomer such as trifluoroethyl acrylate and a monomer such as vinyl naphthalene which has a group containing aromatic chain, simultaneously.